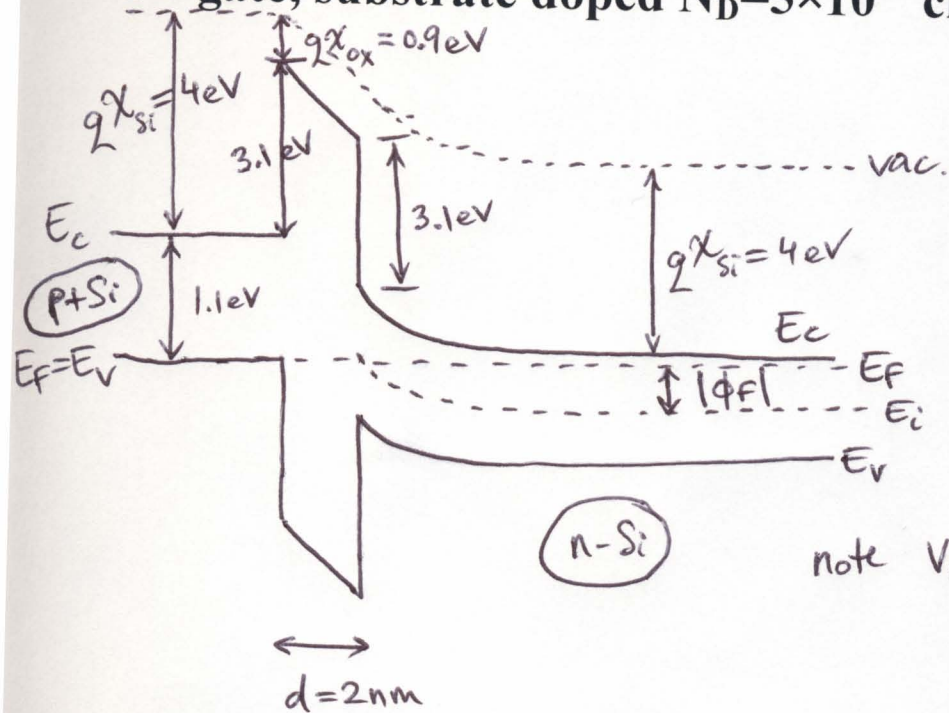


Ex: Plot and label the C-V curve of a PMOS capacitor with P+ gate, substrate doped $N_D = 5 \times 10^{17} \text{ cm}^{-3}$, and SiO_2 $d = 2 \text{ nm}$.



$$C_{ox} = \frac{\epsilon_{ox}}{d} = \frac{3.9 \times 8.854 \times 10^{-14} \text{ F/cm}}{2 \times 10^{-7} \text{ cm}}$$

$$C_{ox} = 1.726 \times 10^{-6} \text{ F/cm}^2$$

$$|\phi_f| = \frac{kT}{q} \ln \frac{N_D}{n_i} \approx 0.45 \text{ V}$$

note $V_{FB} > 0 \leftrightarrow$ must "drag down" Fermi level on gate to reach flat bands ($\mathcal{E} = 0$)

$$V_{FB} = \frac{1}{q} (\phi_{gate} - \phi_{subs}) = \frac{1}{q} (q\chi_{si} + E_g) - \frac{1}{q} (q\chi_{si} + \frac{E_g}{2} - q|\phi_f|)$$

$$= \frac{1}{q} \left(\frac{E_g}{2} + |\phi_f| \right) \approx 0.55 \text{ V} + 0.45 \text{ V} = \boxed{1 \text{ V}}$$

$$V_T = V_{FB} - |2\phi_f| - \frac{1}{C_{ox}} \sqrt{2qN_D\epsilon_{si}|2\phi_f|} = 1 \text{ V} - 0.9 \text{ V} - \frac{\sqrt{2 \times 1.6 \times 10^{-19} \text{ C} \times 5 \times 10^{17} \text{ cm}^{-3} \times 11.9 \times 8.854 \times 10^{-14} \text{ F/cm} \times 0.9 \text{ V}}}{1.726 \times 10^{-6} \text{ F/cm}^2}$$

$$\Rightarrow V_T = 1 \text{ V} - 0.9 \text{ V} - 0.226 \text{ V} = \boxed{-0.126 \text{ V}}$$

$$C_{max} = C_{ox} = 1.726 \times 10^{-6} \text{ F/cm}^2$$

$$C_{min} = \left(\frac{1}{C_{ox}} + \frac{W_{max}}{\epsilon_{si}} \right)^{-1} = \left(\frac{1}{C_{ox}} + \sqrt{\frac{2|2\phi_f|}{qN_D\epsilon_{si}}} \right)^{-1} \approx 1.923 \times 10^{-7} \text{ F/cm}^2$$

